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## (54) PHOTSENSITIVE COMPOSITION

(57)Abstract:

**PURPOSE:** To obtain a photosensitive compsn. ensuring improved applicability and preservability of a photosensitive soln., giving an excellent visible image by exposure and having excellent solubility in a solvent.

**CONSTITUTION:** This photosensitive compsn. contains a fluorine-contg. surfactant made of a copolymer of acrylate or methacrylate (A) contg. a 6-20C fluoro- aliphatic group having  $\geq 30$ wt.% fluorine content with (polyoxyalkylene) acrylate or (polyoxyalkylene) methacrylate (B). The copolymer has 1,000-6,000mol.wt. and contains 10-25wt.% of the monomer A. The fluoro-aliphatic group is preferably a perfectly fluorinated aliphatic group.

## LEGAL STATUS

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